

EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
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L2	31	(detect\$3 sens\$3) near3 (immersion liquid fluid water) same (load\$3 unload \$3) near2 (wafer substrate workpiece) and (\$5lithograph\$2 exposure).ab.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:28
L3	7	(detect\$3 sens\$3) near3 (immersion liquid fluid water) with (table support chuck holder) same (load\$3 unload\$3) near2 (wafer substrate workpiece) with (table support chuck holder) and (\$5lithograph\$2 exposure).ab.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:28
L4	12	(detect\$3 sens\$3) near (immersion liquid fluid water) with (table support chuck holder) same3 (load\$3 unload \$3) near (wafer substrate workpiece) with (table support chuck holder) and (\$5lithograph\$2 exposure).ab.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:28

L5	12	(detect\$3 sens\$3) near (immersion liquid fluid water) with (table support chuck holder) same3 (load\$3 unload \$3) near (wafer substrate workpiece) with (table support chuck holder)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:28
L6	12	(detect\$3 sens\$3 camera determin\$5) near (immersion liquid fluid water) with (table support chuck holder) same3 (load\$3 unload \$3) near (wafer substrate workpiece) with (table support chuck holder)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:28
L7	3	(detect\$3 sens\$3 camera determin\$5) near3 (residual remain \$3 leftover undesir\$4 unwanted stray leak \$3) near (immersion liquid fluid water) with (table support chuck holder) same3 (load\$3 unload\$3) near (wafer substrate workpiece) with (table support chuck holder)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:29
L8	5	(detect\$3 sens\$3 camera determin\$5) near3 (residual remain \$3 leftover undesir\$4 unwanted stray leak \$3) near (immersion liquid fluid water) same10 (load\$3 unload \$3) near (wafer substrate workpiece) with (table support chuck holder)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:29

L9	3	(detect\$3 sens\$3 camera determin\$5) near3 (residual remain \$3 leftover undesir\$4 unwanted stray leak \$3) near (immersion liquid fluid water) same10 (load\$3 unload \$3) near (wafer substrate workpiece) with (table support chuck holder) and (5lithograph\$2 exposure).ab.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:29
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3/10/2011 5:34:50 PM

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detection light liq shape.wsp